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a process chamber that deposits a metal layer on the substrate,  
wherein the substrate is transferred among the chambers in a vacuum while not  
exposed to ambient atmosphere.

### ***Conclusion***

It is respectfully requested that this amendment be entered prior to the examination of the  
above-referenced patent application. It is believed that no new matter is added by this  
amendment. If the Examiner desires any additional information, the Examiner is invited to  
contact applicants' attorney at the telephone number listed below to expedite prosecution.

Respectfully submitted,

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